Title (en)

PHOTOSENSITIVE LACQUER FOR PROVIDING A COATING ON A SEMICONDUCTOR SUBSTRATE OR A MASK

Title (de)

PHOTOSENSITIVER LACK ZUR BESCHICHTUNG AUF EINEM HALBLEITER-SUBSTRAT ODER EINER MASKE

Title (fr)

VERNIS PHOTOSENSIBLE POUR ENDUIRE UN SUPPORT SEMI-CONDUCTEUR OU UN MASQUE

Publication

EP 1509815 A1 20050302 (DE)

Application

EP 03755914 A 20030530

Priority

• DE 0301781 W 20030530
• DE 10224217 A 20020531

Abstract (en)

[origin: WO03102694A1] The invention relates to a photosensitive lacquer (100) for providing a coating on a semiconductor substrate or a mask. The lacquer according to the invention comprises a photosensitive acidifier (D), a solvent (E) and at least two different base polymers. A first base polymer comprises cyclo-aliphatic basic structures (A) which substantially absorb light irradiated thereon at 248 nm and which are substantially transparent to light irradiated at 193 nm. A second base polymer comprises aromatic basic structures (B) which substantially absorb light irradiated thereon at 193 nm and which are substantially transparent to light irradiated at 248 nm. When such a lacquer (100) is applied to a substrate in a layer thickness of 50 to 400 nm and the percentage of the second base polymer comprising the aromatic basic structures is between 1 and 25 mole- %, and when exposed to a wavelength of 193 nm, a higher structure contrast and better etching stability is reached and defects are reduced. Exposure across the entire depth range of the lacquer (100) is likewise ensured.

IPC 1-7

G03F 7/039

IPC 8 full level

G03C 1/492 (2006.01); **G03C 1/494** (2006.01); **G03C 1/76** (2006.01); **G03F 7/039** (2006.01); **H01L 21/31** (2006.01); **H01L 21/469** (2006.01)

CPC (source: EP US)

G03F 7/0392 (2013.01 - EP US); **G03F 7/0395** (2013.01 - EP US)

Citation (search report)

See references of WO 03102694A1

Designated contracting state (EPC)

DE

DOCDB simple family (publication)

WO 03102694 A1 20031211; DE 10224217 A1 20031218; EP 1509815 A1 20050302; US 2005130444 A1 20050616; US 7169716 B2 20070130

DOCDB simple family (application)

DE 0301781 W 20030530; DE 10224217 A 20020531; EP 03755914 A 20030530; US 34204 A 20041129